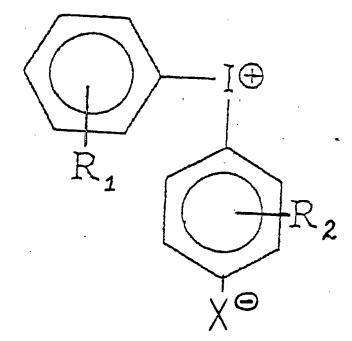
CLAIMS:

1. A zwitterionic compound, comprising:



wherein X⁻ is selected from the group of compounds consisting of: sulfur-containing groups, nitrogen-containing groups, and fluorine-containing groups; and

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wherein R_1 and R_2 are each independently selected from the group consisting of substituted or unsubstituted: alkyls, aryls, halides, and fluorinated alkyls, nitrogen containing groups, halogenated alkyls, alkoxy, aryloxy, halogenated alkoxy, unsaturated alkyls, thioalkyls, unsaturated fluorinated alkyls, unsaturated alkoxy keto alkyls, \mathcal{A} alkoxys, aryloxy, keto aryls, sulfonyl alkyl, sulfonyl aryls.

2. The compound of claim 1 in which X⁻ comprises one of the following entities selected from the group consisting of:

wherein R_{5} is selected from the group consisting of substituted or unsubstituted alkyls, aryls, cycloalkyls, fluorinated alkyls, and fluorinated cycloalkyls.

3. The compound of claim 2 in which X comprises:

4. The compound of claim 2 in which X⁻ comprises:

- 5. The compound of claim 3 in which $R_{\scriptscriptstyle 5}$ is a fluorinated alkyl.
- 6. The compound of claim 5 in which $R_{\scriptscriptstyle 5}$ is a substituted or unsubstituted aryl.
- 7. A diaryl zwitterionic iodonium salt having an iodine atom that is positively charged and an anionic group which comprises either a first substituted arene group designated A_1 or a second

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substituted arene group designated A₂, in which A₁ and A₂ are each independently selected from the group consisting of:

benzene, fluorobenzene, nitrobenzene, benzoic acid, toluene, anisole, iodobenzene, 2-nitroiodobenzene, 3-nitroiodobenzene, 4-nitroiodobenzene, 2-iodobenzoic acid, 3-iodobenzoic acid, 4-iodobenzoic acid, fluoroiodobenzene 4-lodoanisole, 3-acetamidoiodobenzene, and 4-acetamidoiodobenzene;

further wherein either A_1 or A_2 contain an SO_2 -N- SO_2R_5 group substituted upon the arene ring;

wherein R_s is selected from the group consisting of substituted or unsubstituted alkyls, aryls, cycloalkyls, fluorinated alkyls, and fluorinated cycloalkyls.

- 8. The salt compound of claim 7 in which the first arene group A₁ is benzene, and the second arene group A₂ is benzene.
- 9. The salt compound of claim 7 in which the first arene group A₁ is nitrobenzene, and the second arene group A₂ is nitrobenzene.
- 10. The salt compound of claim 7 in which the first arene group A_1 is benzoic acid, and the second arene group A_2 is benzoic acid.
- 11. The salt compound of claim 7 in which the first arene group A_1 is toluene, and the second arene group A_2 is toluene.
- 12. The salt compound of claim 7 in which the first arene group A_1 is anisole, and the second arene group A_2 is anisole.

- 13. The salt compound of claim 7 in which the first arene group A₁ is lodobenzene, and the second arene group A₂ is benzene.
- 14. The salt compound of claim 7 in which the first arene group A_1 is 2-Nitroiodobenzene, and the second arene group A_2 is benzene.
 - 15. The salt compound of claim 7 in which the first arene group A_1 is 3-Nitroiodobenzene, and the second arene group A_2 is benzene.
 - 16. The salt compound of claim 7 in which the first arene group A_1 is 3-Nitroiodobenzene, and the second arene group A_2 is benzene.
 - 17. The salt compound of claim 7 in which the first arene group A_1 is 4-Nitroiodobenzene, and the second arene group A_2 is benzene.
 - 18. The salt compound of claim 7 in which the first arene group A_1 is 2-lodobenzoic acid, and the second arene group A_2 is benzene.
 - 19. The salt compound of claim 7 in which the first arene group A_1 is 3-lodobenzoic acid, and the second arene group A_2 is benzene.
 - 20. The salt compound of claim 7 in which the first arene group A_1 is 4-lodobenzoic acid, and the second arene group A_2 is benzene.

21. A wafer having lithographically etched features on the surface of the wafer, the etched features being adapted for forming an electrical circuit, the etched features having a line width of less
5 than about 0.5μ, whereby the etch is formed in a photoresist process that employs a diaryl zwitterionic iodonium salt.